Three-step lithography to the fabrication of vertically coupled micro-ring resonators in amorphous silicon-on-insulator-corrigendum

Jun Cheng (程 俊)¹ and Duk-Yong Choi²,*

¹School of Electromechanical Engineering, Beijing Institute of Technology, Beijing100081, China
²Centre for Ultrahigh bandwidth Devices for Optical Systems, Laser Physics Centre, Research School of Physics and Engineering, The Australian National University, Canberra, ACT2601, Australia

The authors would like to apologize for three errors in the paper on Chinese Optics Letters vol. 13, no. 8, page 082201.

On page 082201–1, the second author is “Duk-Yong Choi” (not Nan Yan), and the corresponding author is “duk.choi@anu.edu.au” (not Jun Cheng). On page 082201–2, a reference should be added for the Fig. 2 (X. Gai, D.-Y. Choi, and B. Luther-Davies, Opt. Exp. 22, 9948 (2014)). On page 082201–4, line 29, should be “6 and 8 dB/cm” (not 2.6 and 3.2 dB/cm).

doi: 10.3788/COL201614.043501.

References